

PATENT
0171-1063P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: OHSAWA, Youichi et al Conf.:

Appl. No.: NEW Group:

Filed: February 12, 2004 Examiner:

For: NOVEL SULFONYLDIAZOMETHANES, PHOTOACID GENERATORS, RESIST COMPOSITIONS, AND PATTERNING PROCESS

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 12, 2004

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

This amendment includes:

Amendments to the Specification

Remarks